Electrical Characterization of Materials: II

Mark Lundstrom

Electrical and Computer Engineering Purdue University West Lafayette, IN USA





Coupled charge and heat current equations

electrical current:

$$\mathcal{E} = \rho J + S \frac{dT}{dx}$$

heat current (electronic):

$$J_Q = \pi J - \kappa_e \frac{dT}{dx}$$

heat current (lattice):

$$q_x = -\kappa_L \left(\frac{dT}{dx}\right)$$

We have been discussing how to measure conductivity (and carrier density and mobility), and we briefly the Seebeck coefficient.

Outline

1. Review

- 2. Temperature-dependent measurements
- 3. Errors in Hall effect measurements
- 4. Graphene: a case study
- 5. Summary

Hall bar geometry



$$R_{H} = \frac{-V_{H}}{I_{x}B_{z}} = \frac{1}{(-q)(n_{S}/r_{H})}$$

Hall coefficient

$$\frac{V_{21}}{I} = \rho_s \frac{L}{W}$$

$$\mu_H = r_H \mu_n = \frac{1}{n_H q \rho_S}$$

$$r_{H} \equiv \left\langle \left\langle \tau_{m}^{2} \right\rangle \right\rangle / \left\langle \left\langle \tau_{m} \right\rangle \right\rangle^{2}$$

"Hall factor"

van der Pauw geometry



van der Pauw approach: Hall effect



$$V_{H} \equiv \frac{1}{2} \left[V_{PN} \left(+ B_{z} \right) - V_{PN} \left(- B_{z} \right) \right]$$
$$V_{H} = \rho_{n} \mu_{H} B_{z} I$$

So we can do Hall effect measurements on such samples.

See Lundstrom, *Fundamentals of Carrier Transport*, 2nd Ed., Sec. 4.7.1.

van der Pauw approach: resistivity



So we can do resistivity measurements on such samples.

$$R_{MN,OP} = \frac{\rho_{S}}{\pi} \ln\left(\frac{(a+b)(b+c)}{b(a+b+c)}\right)$$
$$R_{NO,PM} = \frac{\rho_{S}}{\pi} \ln\left(\frac{(a+b)(b+c)}{ac}\right)$$

it can be shown that:

$$e^{-\frac{\pi}{\rho_{S}}R_{MN,OP}} + e^{-\frac{\pi}{\rho_{S}}R_{NO,PM}} = 1$$

Given two measurements of resistance, this equation can be solved for the sheet resistance.

van der Pauw technique: regular sample



Force I through two contacts, measure V between the other two contacts.

van der Pauw technique: summary



van der Pauw technique: summary



$$e^{-\frac{\pi}{\rho_{S}}R_{MN,OP}} + e^{-\frac{\pi}{\rho_{S}}R_{NO,PM}} = 1 \qquad \sigma_{S} = n_{S}q\mu_{n} = \frac{n_{S}}{r_{H}}qr_{H}\mu_{n} = n_{H}q\mu_{H}$$

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Temperature-dependent measurements

It is common practice to measure the temperature-dependent conductivity.

Assuming that the carrier density is known (or can be measured), a mobility is then extracted from: $\sigma = n q \mu_n$



Interpretation



Charged impurity scattering



Random charges introduce random fluctuations in E_c , which act a scattering centers.

High energy electrons don't "see" these fluctuations and are not scattered as strongly.

Average carrier energy ~ $k_B T_L$.

Mobility should increase with increasing temperature.

LAttice (phonon) scattering

$$\frac{1}{\tau(E)} \propto n_{ph}$$
$$n_{ph} = \frac{1}{e^{h\omega/k_B T_L} - 1}$$
$$n_{ph} \uparrow \text{ as } T_L \uparrow$$

Carrier scattering rate is proportional to the number of phonons.

Phonon occupation number given by the Bose-Einstein distribution.

Number of phonons increases as temperature increase. Scattering time decreases.

Mobility should decrease with increasing temperature.

Mobility vs. temperature



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Hall effect measurements (errors)



We have assumed isothermal conditions to compute the Hall voltage, but we expect Peltier cooling at contact 0 and Peltier heating at contact 1. If the sample is not isothermal, how does the Hall voltage change?

Magnetoconductivity tensor

$$\begin{pmatrix} J_{nx} \\ J_{ny} \end{pmatrix} = \begin{pmatrix} \sigma_{s} & -\sigma_{s}\mu_{H}B_{z} \\ +\sigma_{s}\mu_{H}B_{z} & \sigma_{s} \end{pmatrix} \begin{pmatrix} \mathcal{E}_{x} \\ \mathcal{E}_{y} \end{pmatrix}$$
$$J_{ni} = \sum_{j} \sigma_{ij} \begin{pmatrix} B_{z} \end{pmatrix} \mathcal{E}_{j} \qquad \begin{pmatrix} \sigma_{11} & \sigma_{12} \\ \sigma_{21} & \sigma_{22} \end{pmatrix} = \begin{pmatrix} \sigma_{s} & -\sigma_{s}\mu_{H}B_{z} \\ +\sigma_{s}\mu_{H}B_{z} & \sigma_{s} \end{pmatrix}$$

 $J_{ni} = \sigma_{ij} (B_z) \mathcal{E}_j$ (summation convention)

 $\mathcal{E}_{ijk} = +1(i, j, k \text{ cyclic})$ $J_i = \sigma_s \mathcal{E}_i - \sigma_s \mu_H \mathcal{E}_{ijk} \mathcal{E}_j B_k = -1(i, j, k \text{ anti-cyclic})$ = 0 (otherwise)

Recall...

$$\mathcal{E}_{i} = \rho_{ij} \left(\vec{B} \right) J_{j} + S_{ij} \left(\vec{B} \right) \partial_{j} T_{L}$$
$$J_{i}^{Q} = \pi_{ij} \left(\vec{B} \right) J_{j} - \kappa_{ij}^{e} \left(\vec{B} \right) \partial_{j} T_{L}$$

$$\rho_{ij}\left(\vec{B}\right) = \rho_0 + \rho_0 \mu_H \varepsilon_{ijk} B_k + \dots$$
$$S_{ij}\left(\vec{B}\right) = S_0 + S_1 \varepsilon_{ijk} B_k + \dots$$
$$\pi_{ij}\left(\vec{B}\right) = \pi_0 + \pi_1 \varepsilon_{ijk} B_k + \dots$$
$$\kappa_{ij}^e\left(\vec{B}\right) = \kappa_0^e + \kappa_1 \varepsilon_{ijk} B_k + \dots$$

For parabolic energy bands

Nernst effect

Assume that there is a temperature gradient in the *x*-direction. How is the electric field (Hall voltage) affected?)

 $\mathcal{E}_{y} = \rho_{0}J_{y} + \rho_{0}\mu_{H}\varepsilon_{yjz}B_{z}J_{j} + S_{0}\partial_{y}T_{L} + S_{1}\varepsilon_{yjz}B_{z}\partial_{j}T_{L}$



Nernst voltage Reverse direction of B_z and J_x and average results to eliminate.

Other effects

Other "thermomagnetic effects" such as the Ettingshaussen and Righi-Leduc effects also occur and affect the measured Hall voltage. See Lundstrom, Chapter 4, Sec. 4.6.2 for a discussion.

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Taken from: 2011 NCN Summer School, "Near-equilibrum Transport, Lecture 10: Case study-Near-equilibrium Transport in Graphene," http://nanohub.org/resources/11873

Graphene



$$D(E) = 2|E|/\pi\hbar^{2}\upsilon_{F}^{2}$$

$$n_{S}(E_{F}) = \int_{0}^{\infty} D(E)f_{0}(E)dE \approx \frac{E_{F}^{2}}{\pi\hbar^{2}\upsilon_{F}^{2}}$$

$$M(E) = W\frac{2|E|}{\pi\hbar\upsilon_{F}}$$

$$\sigma_{S}(OK) = \frac{2q^{2}}{h}\lambda_{app}\left(\frac{2E_{F}}{\pi\hbar\upsilon_{F}}\right)$$

$$\frac{1}{\lambda_{app}} = \frac{1}{\lambda(E_{F})} + \frac{1}{L}$$

- The location of the Fermi level (or equivalently the carrier density) is experimentally controlled by a "gate."
- 2) In a typical experiments, a layer of graphene is placed on a layer of SiO_2 , which is on a doped silicon substrate. By changing the potential of the Si substrate (the "back gate"), the potential in the graphene can be modulated to vary E_F and, therefore, n_S .

Experimental structure (2-probe)

(4-probe techniques are used to eliminate series resistance and for Hall effect measurements.)



Side

Top view

Typically, Cr/Au or Ti/Au are used for the metal contacts.

The thickness of SiO_2 is typically 300nm or 90nm, which makes it possible to see a single layer of graphene.

Using a gate voltage to change the Dirac point (or E_F)



Gate voltage - carrier density relation



If the oxide is not too thin (so that the quantum capacitance of the graphene is not important), then

$$qn_S = C_{ins}V_G'$$

$$C_{ins} = \frac{\mathcal{E}_{ins}}{t_{ins}}$$

Sheet conductance vs. V_G



Fig. 30 in A. H. Castro, et al., "The electronic properties of graphene," Rev. of Mod. Phys., **81**, 109, 2009.

$$G = \sigma_{s} W/L$$

$$\sigma_{S}(E_{F}) \approx \frac{2q^{2}}{h} \lambda_{app} \left(E_{F} \right) \left(\frac{2E_{F}}{\pi \hbar \upsilon_{F}} \right)$$
$$n_{S} = C_{ox} V_{G} \approx \frac{1}{\pi} \left(\frac{E_{F}}{\hbar \upsilon_{F}} \right)^{2}$$

$$\lambda_{app}\left(E_{F}
ight)\!=\!rac{\sigma_{_{S}}/\!\left(2q^{_{2}}/h
ight)}{2\sqrt{n_{_{S}}/\pi}}$$

 $(T_L = 0 \mathrm{K})$

Mean-free-path (V_G = 100V)



Fig. 30 in A. H. Castro, et al., "The electronic properties of graphene," Rev. of Mod. Phys., 81, 109, 2009. $\lambda(0.3 \,\mathrm{eV}) \ll L$

Mean-free-path ($V_G = 50V$)



 $\lambda(E_F) \propto E_F$

Mobility



Fig. 30 in A. H. Castro, et al., "The electronic properties of graphene," Rev. of Mod. Phys., **81**, 109, 2009.

Since, $\sigma_{\rm S} \sim n_{\rm S}$, we can write:

$$\sigma_{S} \equiv n_{S} q \mu_{n}$$

and deduce a mobility:

 $\mu_n \approx 12,500 \text{ cm}^2/\text{V-sec}$

Mobility is constant, but meanfree-path depends on the Fermi energy (or n_s).

Electron-hole puddles



Fig. 30 in A. H. Castro, et al., "The electronic properties of graphene," Rev. of Mod. Phys., **81**, 109, 2009.

J. Martin, et al, "Observation of electron–hole puddles in graphene using a scanning single-electron transistor," Nature Phys., **4**, 144, 2008



J.-H. Chen, C. Jang, S. Adam, M. S. Fuhrer, E. D. Williams, and M. Ishigami, "Charged-impurity scattering in graphene," *Nature Phys.*, **4**, 377-381, 2008.

Nominally undoped sample: is it ballistic?



J.-H. Chen, C. Jang, S. Adam, M. S. Fuhrer, E. D. Williams, and M. Ishigami, "Charged-impurity scattering in graphene," *Nature Phys.*, **4**, 377-381, 2008.

Unannealed vs. annealed suspended graphene



K. I. Bolotin, K. J. Sikes, J. Hone, H. L. Stormer, and P. Kim, "Temperature dependent transport in suspended graphene," 2008

Temperature dependence

Away from the conductance minimum, the conductance decreases as T_L increases (or resistivity increases as temperature increases).



 $T_L < 100K: R_S \propto T_L$

(acoustic phonon scattering - intrinsic)

$$T_L > 100K$$
: $R_S \propto e^{\hbar\omega_0/k_B T_L}$

(optical phonons in graphene or surface phonons at SiO₂ substrate)

J.-H. Chen, J. Chuan, X. Shudong, M. Ishigami, and M.S. Fuhrer, "Intrinsic and extrinsic performance limits of graphene devices on SiO₂," Nature Nanotechnology, **3**, pp. 206-209, 2008.

Phonons and temperature dependence

$$R_{S} = \frac{1}{G_{S}} \propto \frac{1}{\lambda} \propto \frac{1}{\tau} \propto n_{0}$$

$$n_0 = \frac{1}{e^{h\omega(\beta)/k_B T_L} - 1}$$

acoustic phonons:

optical phonons:

$$\hbar\omega_{0}\approx k_{B}T_{L}$$

$$n_0 = \frac{1}{e^{h\omega_0/k_B T_L} - 1}$$
$$R_S \propto \frac{1}{e^{h\omega_0/k_B T_L} - 1}$$

 $\hbar\omega < k_{_B}T_{_L}$

$$N_{\beta} \approx \frac{k_{B}T_{L}}{h\omega}$$

$$R_S \propto T_L$$

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Summary

- Hall bar or van der Pauw geometries allow measurement of both resistivity and Hall concentration from which the Hall mobility can be deduced.
- 2) Temperature-dependent measurements provide information about the dominant scattering mechanisms.
- 3) Care must be taken to exclude thermoelectric effects.

References

Kasper A. Borup, Johannes de Boor, Heng Wang,cFivos Drymiotis, Franck Gascoin, Xun Shi, Lidong Chen, Mikhail I. Fedorov, Eckhard Muller,Bo B. Iversen, and G. Jeffrey Snyder, "Measuring thermoelectric transport properties of Materials," *Energy & Environmental Science*, **8**, 423–435, 2015.

Questions

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